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FABRICATION OF THIN FILM TIN OXIDE GAS SENSORS BY SOL-GEL TECHNIQUE

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วิทยานิพนท์นี้เป็นการศึกษาการประดิษฐ์หัวครวจก๊าซแบบฟิล์มบางของดีบุกออกไซด์โดยใช้เทคนิคโซล-เจล สารละลายโซลของดีบุกออกไซด์ได้ถูกเตรียมด้วยกระบวนการสังเคราะห์ทางเคมี โดยที่มีดีบุกเตตระคลอไรด์และโซเดียมเอ ขอไซด์เป็นสารเริ่มต้นหลักในการทำปฏิกิริยา ฟิล์มบางของดีบุกออกไซด์จะถูกเตรียมโดยการนำสารละลายโซลที่ได้จะนำไป เคลือบลงบนแผ่นฐานรองที่เป็นกระจกด้วยเทคนิคการสปินโคทติง แล้วจึงเผาด้วยความร้อนที่อุณหภูมิ 550°C เป็นเวลา เชิ่วโมง เพื่อเปลี่ยนโครงสร้างให้เป็นดีบุกออกไซด์ จากการศึกษาพบว่าความหนาของชั้นดีบุกออกไซด์สามารถควบคุมใน ลักษณะเชิงเส้นโดยการแปรจำนวนครั้งของการเคลือบ โดยมีความหนาของการเคลือบ 1 ครั้ง เท่ากับ 350 อังสตรอม

เพื่อให้การวิเคราะห์หาประสิทธิภาพการตอบสนองของหัวตรวจวัดก็าชที่ได้ประดิษฐ์ขึ้นเป็นไปอย่างถูกต้อง ได้มีการนำเสนอวงจรวัดแบบใหม่ที่สามารถนำมาใช้กำนวณหาค่าความไวและค่าเวลาพื้นตัวของหัวตรวจวัดก็าชได้อย่างถูก ต้องโดยไม่ขึ้นกับค่าของอุปกรณ์ภายนอกที่มาต่อ เช่น ค่าความด้านทาน ได้มีการเปรียบเทียบระหว่างวงจรแบบที่นำเส่นอกับ วงจรวัดแบบเดิมในแง่ของการวิเคราะห์ทางทฤษฎีและการทดลอง ผลที่ได้ชี้ให้เห็นว่าวงจรวัดแบบเดิมนั้นไม่เหมาะสมกับการใช้หาค่าความไวในกรณีที่หัวตรวจวัดก็าชมีลักษณะสมบัติของกระแส-แรงดันแบบไม่เชิงเส้น ส่วนในกรณีของวงจรแบบใหม่ จะไม่พบปัญหาดังกล่าว นอกจากนี้เมื่อกำหนดให้แรงดันไบอัสของหัวตรวจวัดก็าชมีค่าเท่ากันแล้วจะสามารถเปรียบเทียบค่า ความไวและค่าเวลาพื้นตัวของหัวตรวจวัดก็าชได้อย่างถูกต้อง

โดยการใช้วงจรวัดแบบใหม่กับระบบวัดก๊าซแบบโฟลว์อินเจคชันวัดลักษณะสมบัติการตอบสนองของหัวตรวจ วัดก๊าซที่ได้ประดิษฐ์พบว่า ความหนาของฟิล์มบางคีบุกออกไซด์มีผลอย่างมากต่อค่าความไวของหัวตรวจวัดก๊าซ ความหนาที่ เหมาะสมของฟิล์มบางมีค่าอยู่ประมาณ 1000 อังสตรอม จากการวัดการตอบสนองที่มีต่อสารละถายของแอลกอฮอล์และ แอมโมเนีย พบว่า หัวตรวจวัดก๊าซของดีบุกออกไซด์ที่ไม่มีการเดิมสารเจือปนให้ค่าความไวสูงสุด การเดิมสารเจือปนของทอง แดงซัลเฟต ทองและเงินคลอไรด์จะทำให้ค่าความไวของหัวตรวจวัดก๊าซลดลง แต่การเดิมเหล็กคลอไรด์มีแนวไน้มที่จะแสดงให้เห็นว่าความไวมีค่าสูงขึ้น การวิเคราะห์โดยใช้ไมเดลของกฎการยกกำลังแสดงให้เห็นว่า หัวตรวจวัดก๊าซของดีบุกออกไซด์ที่ ไม่มีการเดิมสารเจือปนจะสามารถตอบสนองแบบเชิงเส้นต่อแอลกอฮอล์ในช่วงความเข้มขึ้นร้อยละ 0.08-10 โดยปริมาตร และ ต่อแอมโมเนียในช่วงความเข้มขึ้นร้อยละ 0.05 - 10 โดยปริมาตรสำหรับ อุณหภูมิการทำงานที่เหมาะสมของหัวตรวจวัดก๊าซ

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	วิสวกรรมไฟห้า	ลายมือชื่ออาจารย์ที่ปรึกษา
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ARPORN TEERAMONGKONRASMEE: FABRICATION OF THIN FILM TIN OXIDE GAS SENSORS BY SOL-GEL TECHNIQUE. DISSERTATION ADVISOR: ASSC. PROF. MANA SRIYUDTHSAK, D. Eng. DISSERTATION CO-ADVISOR: PROF. TOYOSAKA MORIIZUMI, D. Eng. 161 pp. ISBN 974-331-253-6.

In this dissertation, a systematic study involving the fabrication of thin film SnO₂ gas sensors by sol-gel technique had been carried out. The sol solution of SnO₂ was prepared by chemical synthesis process. Tin tetrachloride and sodium ethoxide were used as the fundamental reactants. The synthesis sol had been coated on the glass substrate by spin coating technique to form thin films. The coated films were then subjected to anneal at 550 °C for 1 hour to change their structure to SnO₂. It was found that the thickness of SnO₂ films could be linearly controlled by varying the number of coatings. The thickness of each coating was about 350 Å.

In order to analyze the gas sensing performance quantitatively, a novel gas measuring circuit was proposed. This circuit could be used to calculate sensitivity and recovery time without depending on the external circuit components such as resistance. The performance of this proposed circuit had been compared with that of the conventional circuit in both theoretical and experiment aspects. The results indicated the conventional measuring circuit is not suitable for calculating gas sensitivity in the case which a semiconductor gas sensor under test has a nonlinear *I-V* characteristic. For the proposed circuit, this nonlinear property did not cause any problem in calculating sensitivity. Moreover, the gas sensing performance of various gas sensors could be compared quantitatively if the bias voltage of all gas sensors were set to the same value.

The characterization of the fabricating gas sensors had been performed on a flow injection system combining with the proposed measuring circuit. The sensitivity of gas sensor had been found to be strongly dependent on the film thickness. The experiments showed that the optimum thickness was about 1000 Å. From the gas response tests to alcohol and ammonia solutions, it was found that the unmodified SnO₂ gas sensor gave the highest sensitivity. The addition of some modified substances such as CuSO₄, AgNO₃ and Au reduced the gas sensitivity. However, there was a tendency to increase sensitivity by adding FeCl₃. By using the power law model to analyze the change of sensitivity with sample concentration, it was found that the unmodified SnO₂ gas sensor could be used to detect alcohol and ammonia in the range of 0.08 - 10 and 0.05 - 10 % by volume respectively. The optimum operating temperature was 250°C for alcohol detection and 350°C ammonia detection.

ภาควิชาวิสวกรรมไฟฟ้า	ลายมือชื่อนิสิต <u>สาวะก</u> า	Tecramonskonramue
สาขาวิชาวิสวกรรมไฟฟ้า	ลายมือชื่ออาจารย์ที่ปรึกษา	



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List of Symbols and Acronyms

Acronyms

CVD Chemical vapor deposition

EB Electron beam evaporator

Gas FET Gas sensitive field effect transistor

HC Hydrocarbon

HP Hydrophobic silica

TEM Transmission electron microscope

TM Trimethylchlorosilane

XPS X-ray photoelectron spectroscopy

Fundamental constants

\mathcal{E}_0	Permittivity in free space	$8.854 \times 10^{-12} \mathrm{F m^{-1}}$

k Boltzmann constant $1.381 \times 10^{-23} \text{ J K}^{-1}$

q elementary charge 1.602×10^{-19} C

Symbols

£	Dielectric constant

 θ Surface coverage

 σ Conductivity

φ Work function

α Non-linear coefficient

au Time constant

C Capacitance

C_s Sensor capacitance

d Density

D Grain diameter

Symbols (continued)

$D_{a u}$	Estimated grain size
E	Energy
E_{c}	Conduction band edge
E_{F}	Fermi energy level
E_{v}	Valence band edge
\boldsymbol{G}	Conductance
I	Current
I_{o}	Reverse saturation current
n	Electron concentration
N_{A}	Acceptor concentration
$N_{ m D}$	Donor concentration
N_{s}	Surface charge density
p	Hole concentration
P	Pressure
R	Resistance
R_{s}	Sensor resistance
S	Sensitivity
S_{av}	Specific surface area
T	Absolute temperature
$t_{\rm r}$	Recovery time
V	Potential
$V_{ m in}$	Voltage source
$V_{\rm o}$	Contact potential
V_{s}	Voltage across gas sensor
W	Thickness of space-charge layer